

L Number	Hits	Search Text	DB	Time stamp
1	2	("20020119398").PN.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/03/09 15:17
2	40	impd! (integrated adj microelectronic adj process adj device)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/03/09 15:18
3	296802	co2 "co.sub.2" carbon adj dioxide	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/03/09 15:19
4	434298	resist photoresist photo-resist	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/03/09 15:39
5	331011	photosensitive photo-sensitive (sensitive near (photo light energy radiation))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/03/09 15:40
6	1748023	polymer polymeric monomer oligomer fluoropolymer\$3 fluoro-polymer\$3	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/03/09 16:08
7	218	DESIMONE-J-.in. DESIMONE-JOSEPH-.in. DESIMONE-JOSEPH-M-.in. DESIMONE-J-M-.in. CARBONELL-RUBEN-.in. CARBONELL-RUBEN-G-.in. CARBONELL-RUBEN-GUILLERMO-.in. CARBONELL-R-C-.in. KENDALL-JONATHAN-.in. KENDALL-JONATHAN-L-.in. KENDALL-JONATHAN-M-.in. KENDALL-JONATHAN-MARK-.in. MCADAMS-CHRISTOPHER-L-.in.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/03/09 16:26
8	8481	430/311, 313, 314, 322, 323, 324, 925.ccls. 427/489, 490.ccls. 216/62.ccls.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/03/09 16:15
9	163	(co2 "co.sub.2" carbon adj dioxide) and (DESIMONE-J-.in. DESIMONE-JOSEPH-.in. DESIMONE-JOSEPH-M-.in. DESIMONE-J-M-.in. CARBONELL-RUBEN-.in. CARBONELL-RUBEN-G-.in. CARBONELL-RUBEN-GUILLERMO-.in. CARBONELL-R-C-.in. KENDALL-JONATHAN-.in. KENDALL-JONATHAN-L-.in. KENDALL-JONATHAN-M-.in. KENDALL-JONATHAN-MARK-.in. MCADAMS-CHRISTOPHER-L-.in.) (430/311, 313, 314, 322, 323, 324, 925.ccls. 427/489, 490.ccls. 216/62.ccls.) and ((resist photoresist photo-resist) (photosensitive photo-sensitive (sensitive near (photo light energy radiation))) (polymer polymeric monomer oligomer fluoropolymer\$3 fluoro-polymer\$3)) and (co2 "co.sub.2" carbon adj dioxide)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/03/09 16:42
11	352	((resist photoresist photo-resist) (photosensitive photo-sensitive (sensitive near (photo light energy radiation)))) with (polymer polymeric monomer oligomer fluoropolymer\$3 fluoro-polymer\$3) with (co2 "co.sub.2" carbon adj dioxide)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/03/09 16:39
14	106		USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/03/09 16:49

17	1	((resist photoresist photo-resist) (photosensitive photo-sensitive (sensitive near (photo light energy radiation))) with (polymer polymeric monomer oligomer fluoropolymer\$3 fluoro-polymer\$3) with (co2 "co.sub.2" carbon adj dioxide) with (film coating layer)) same ((co2 "co.sub.2" carbon adj dioxide) near3 develop\$5)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/03/09 16:50
15	39	((resist photoresist photo-resist) (photosensitive photo-sensitive (sensitive near (photo light energy radiation))) with (polymer polymeric monomer oligomer fluoropolymer\$3 fluoro-polymer\$3) with (co2 "co.sub.2" carbon adj dioxide) with (film coating layer) (co2 "co.sub.2" carbon adj dioxide) near3 develop\$5	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/03/09 17:29
16	1286	((resist photoresist photo-resist) (photosensitive photo-sensitive (sensitive near (photo light energy radiation))) with (polymer polymeric monomer oligomer fluoropolymer\$3 fluoro-polymer\$3) with (co2 "co.sub.2" carbon adj dioxide) with (film coating layer) (co2 "co.sub.2" carbon adj dioxide) near3 develop\$5	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/03/09 16:51
19	1	((resist photoresist photo-resist) (photosensitive photo-sensitive (sensitive near (photo light energy radiation))) with (polymer polymeric monomer oligomer fluoropolymer\$3 fluoro-polymer\$3) with (co2 "co.sub.2" carbon adj dioxide) with (film coating layer)) same (((co2 "co.sub.2" carbon adj dioxide) near3 develop\$5) with ((resist photoresist photo-resist) (photosensitive photo-sensitive (sensitive near (photo light energy radiation)) (polymer polymeric monomer oligomer fluoropolymer\$3 fluoro-polymer\$3)))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/03/09 17:30
20	2	((resist photoresist photo-resist) (photosensitive photo-sensitive (sensitive near (photo light energy radiation))) with (polymer polymeric monomer oligomer fluoropolymer\$3 fluoro-polymer\$3) with (co2 "co.sub.2" carbon adj dioxide) with (film coating layer)) and (((co2 "co.sub.2" carbon adj dioxide) near3 develop\$5) with ((resist photoresist photo-resist) (photosensitive photo-sensitive (sensitive near (photo light energy radiation)) (polymer polymeric monomer oligomer fluoropolymer\$3 fluoro-polymer\$3)))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/03/09 16:52
18	67	((co2 "co.sub.2" carbon adj dioxide) near3 develop\$5) with ((resist photoresist photo-resist) (photosensitive photo-sensitive (sensitive near (photo light energy radiation)) (polymer polymeric monomer oligomer fluoropolymer\$3 fluoro-polymer\$3))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/03/09 17:06
22	152727	cvd! (chemical\$3 adj vapor adj deposit\$5)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/03/09 17:29

23	19	((resist photoresist photo-resist) (photosensitive photo-sensitive (sensitive near (photo light energy radiation))) (polymer polymeric monomer oligomer fluoropolymer\$3 fluoro-polymer\$3)) with (co2 "co.sub.2" carbon adj dioxide) with (film coating layer)) same ((co2 "co.sub.2" carbon adj dioxide) near3 develop\$5) with ((resist photoresist photo-resist) (photosensitive photo-sensitive (sensitive near (photo light energy radiation))) (polymer polymeric monomer oligomer fluoropolymer\$3 fluoro-polymer\$3))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/03/09 17:30
25	101	((resist photoresist photo-resist) (photosensitive photo-sensitive (sensitive near (photo light energy radiation))) (polymer polymeric monomer oligomer fluoropolymer\$3 fluoro-polymer\$3)) near2 (co2 "co.sub.2" carbon adj dioxide) near2 (film coat\$3 layer deposit\$5 contact\$3)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/03/09 17:35
26	4	((resist photoresist photo-resist) (photosensitive photo-sensitive (sensitive near (photo light energy radiation))) (polymer polymeric monomer oligomer fluoropolymer\$3 fluoro-polymer\$3)) near2 (co2 "co.sub.2" carbon adj dioxide) near2 (film coat\$3 layer deposit\$5 contact\$3)) with (expos\$4 irradiat\$5 light radiation)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/03/09 17:35
27	18	((resist photoresist photo-resist) (photosensitive photo-sensitive (sensitive near (photo light energy radiation))) near2 (co2 "co.sub.2" carbon adj dioxide) near2 (film coat\$3 layer deposit\$5 contact\$3)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/03/09 17:39
28	2	((co2 "co.sub.2" carbon adj dioxide) near3 develop\$5) with ((resist photoresist photo-resist) (photosensitive photo-sensitive (sensitive near (photo light energy radiation))) (polymer polymeric monomer oligomer fluoropolymer\$3 fluoro-polymer\$3)) and ((resist photoresist photo-resist) (photosensitive photo-sensitive (sensitive near (photo light energy radiation))) near2 (co2 "co.sub.2" carbon adj dioxide) near2 (film coat\$3 layer deposit\$5 contact\$3))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/03/09 17:40
30	10	((resist photoresist photo-resist) (photosensitive photo-sensitive (sensitive near (photo light energy radiation))) (polymer polymeric monomer oligomer fluoropolymer\$3 fluoro-polymer\$3)) with (co2 "co.sub.2" carbon adj dioxide) with (cvd! (chemical\$3 adj vapor adj deposit\$5))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/03/09 17:43
31	22	(("5665527") or ("5523163") or ("5116637") or ("5547703") or ("5262201") or ("6231989") or ("5739223") or ("6001418") or ("6045877") or ("4749631") or ("4756977") or ("4847162") or ("4842888") or ("6074695") or ("5618878") or ("5753305") or ("6024801") or ("6165559") or ("5733714") or ("5468595") or ("6265129") or ("3858304")).PN. ("4636440").PN.	USPAT	2004/03/09 17:46
32	1	USPAT	2004/03/09 17:46	

33	23	((("5665527") or ("5523163") or ("5116637") or ("5547703") or ("5262201") or ("6231989") or ("5739223") or ("6001418") or ("6045877") or ("4749631") or ("4756977") or ("4847162") or ("4842888") or ("6074695") or ("5618878") or ("5753305") or ("6024801") or ("6165559") or ("5733714") or ("5468595") or ("6265129") or ("3858304")).PN.) (("4636440").PN.)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/03/09 17:46
34	6	((("5665527") or ("5523163") or ("5116637") or ("5547703") or ("5262201") or ("6231989") or ("5739223") or ("6001418") or ("6045877") or ("4749631") or ("4756977") or ("4847162") or ("4842888") or ("6074695") or ("5618878") or ("5753305") or ("6024801") or ("6165559") or ("5733714") or ("5468595") or ("6265129") or ("3858304")).PN.) (("4636440").PN.)) and (co2 "co.sub.2" carbon adj dioxide)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/03/09 17:49
35	6	((("5665527") or ("5523163") or ("5116637") or ("5547703") or ("5262201") or ("6231989") or ("5739223") or ("6001418") or ("6045877") or ("4749631") or ("4756977") or ("4847162") or ("4842888") or ("6074695") or ("5618878") or ("5753305") or ("6024801") or ("6165559") or ("5733714") or ("5468595") or ("6265129") or ("3858304")).PN.) (("4636440").PN.)) and (co2 "co.sub.2" carbon adj dioxide)) and (develop\$5 (resist photoresist photo-resist) (photosensitive photo-sensitive (sensitive near (photo light energy radiation))) coat\$3 deposit\$5)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/03/09 17:50